







## Impact of the ERL Beam Loading Patterns on the RF system and BBU Instabilities

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ERL cavity voltage, RF power, and BBU threshold currents are beam loading pattern dependent **Optimal pattern can lower cavity voltage fluctuation and power consumption and increase threshold current** 



## Pattern dependance

• V<sub>cav</sub> and P<sub>amp</sub> are pattern dependent

 Some patterns have stabler cavity voltage and requires less amplifier powers

• FF lowers power consumption





Pattern #1: {1,2,3,4,5,6} Pattern #2: {1,2,3,4,6,5} Pattern #120: {1,6,5,4,2,1}

Beam Breakup (BBU) instabilities

1. Offset  $x_n$  causes HOM:  $V_{HOM,R} = \frac{\omega_{HOM}^2}{2c} q_b \left(\frac{R}{Q}\right)$  $x_{n}$ 

BBU Positive feedback loop: Offset  $\rightarrow$  HOMs  $\rightarrow$  Kick  $\rightarrow$  Off-set  $\rightarrow$  ...







•  $I_{test} = I_{th} \rightarrow V_{HOM}$  stable

t (μs)

## BBU pattern dependance









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